Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuB2] Sustainable Etch	
Session Date	November 11 (Tue.), 2025
Session Time	14:50-16:05
Session Room	Room B (Grand Ballroom 1, 2F)
Session Chair	Dr. Thorsten Lill (Lam Research, USA)

[TuB2-1] [Invited] **14:50-15:20**

Low-GWP Cyclic Etching of SiO_2 Contact Holes Using Heptafluoropropyl Methyl Ether

Sanghyun You and Chang-Koo Kim (Ajou Univ., Korea)

[TuB2-2] **15:20-15:35**

Low Global Warming $C_5F_{10}O/H_2O$ Plasma for Low Temperature Etching of SiO_2 and Si_3N_4

Daeun Hong, Sumin Park, Eunsu Lee, and Heeyeop Chae (Sungkyunkwan Univ., Korea)

[TuB2-3] **15:35-15:50**

Comparative Study of C_3F_6 and CF_4 for Sustainable Plasma Etching of SiO_2

Inkyoung Cho and Chang-Koo Kim (Ajou Univ., Korea)

[TuB2-4] **15:50-16:05**

Comparison of Etching Characteristics and Environmental Impact of Fluorocarbon Isomers in High Aspect Ratio (HAR) Etching Processes

Seyoung Choi, Chanhyuk Choi, Myeongho Park, Junsoo Lee, Akihide Sato, Sungtaek Kim, Dongwoo Kim, and Geunyoung Yeom (Sungkyunkwan Univ., Korea)